

17th International Conference on Atomic Layer Deposition Denver, Colorado, USA 2017

What theory can tell us about ALD mechanism

Simon D. Elliott & co-workers



simon.elliott@tyndall.ie

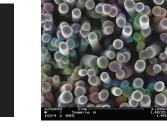


The length scales of ALD

metre

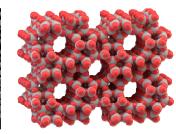
micro

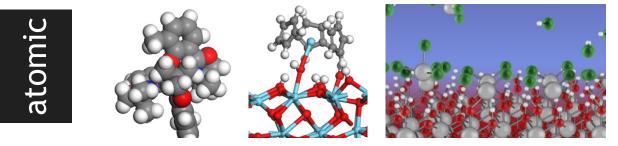
nano

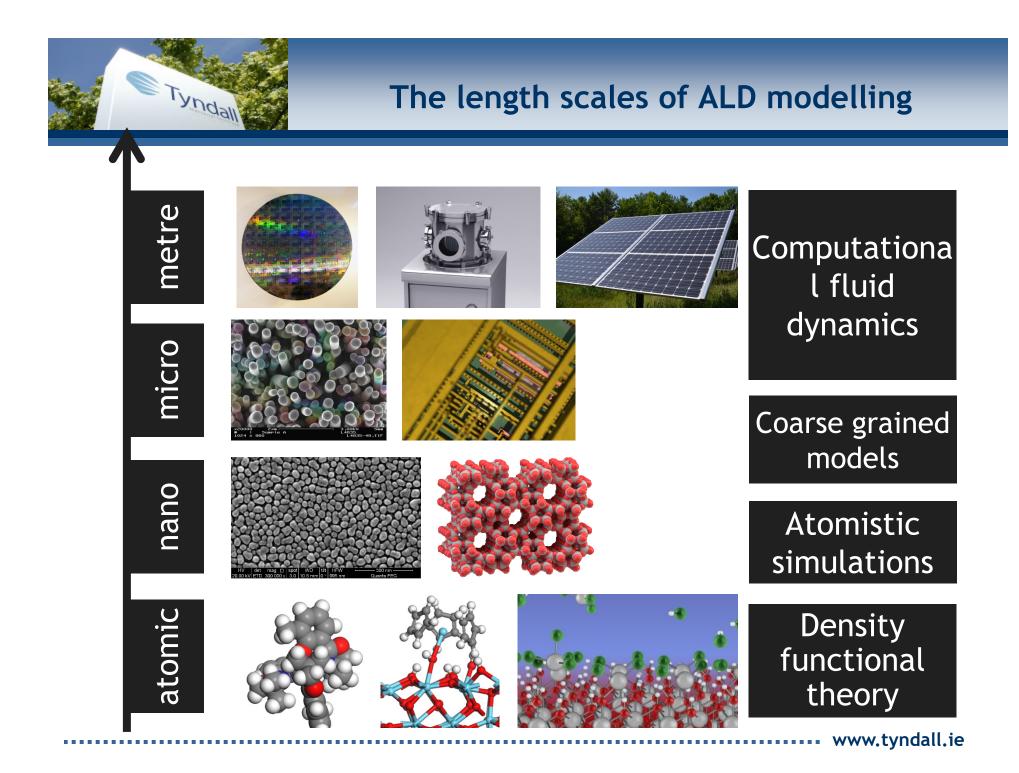






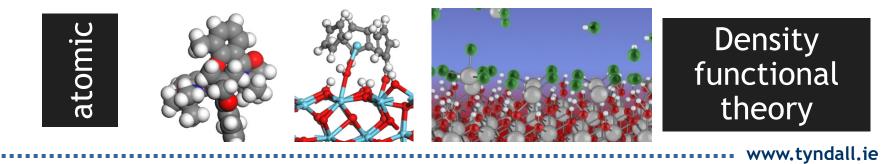






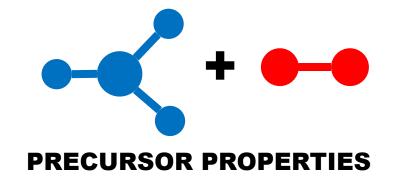


Atomic scale modelling for ALD



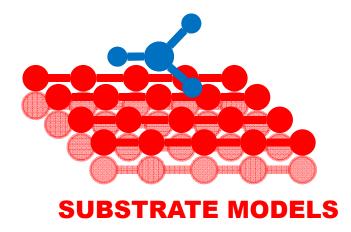


Precursor molecules





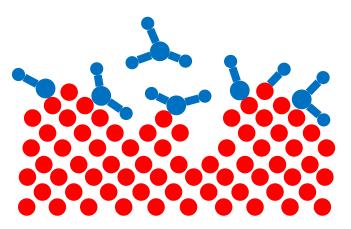
Adsorption onto simple surfaces





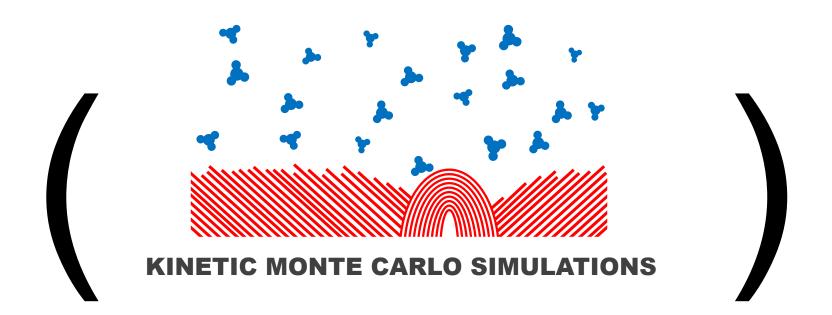
Adsorbates on 3D-structured surfaces

MULTIPLE ADSORBATES



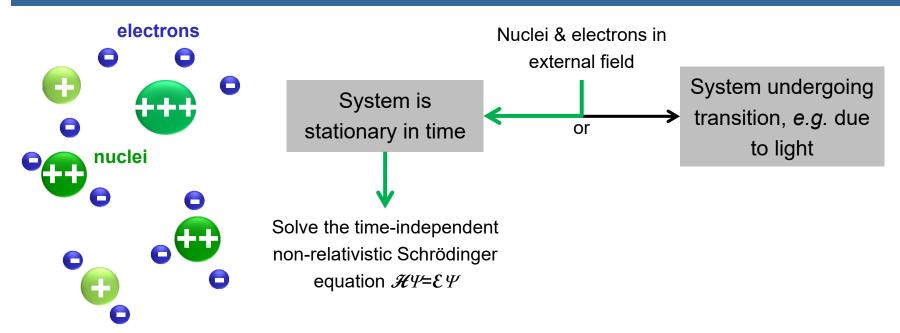


Gas flow and film morphology



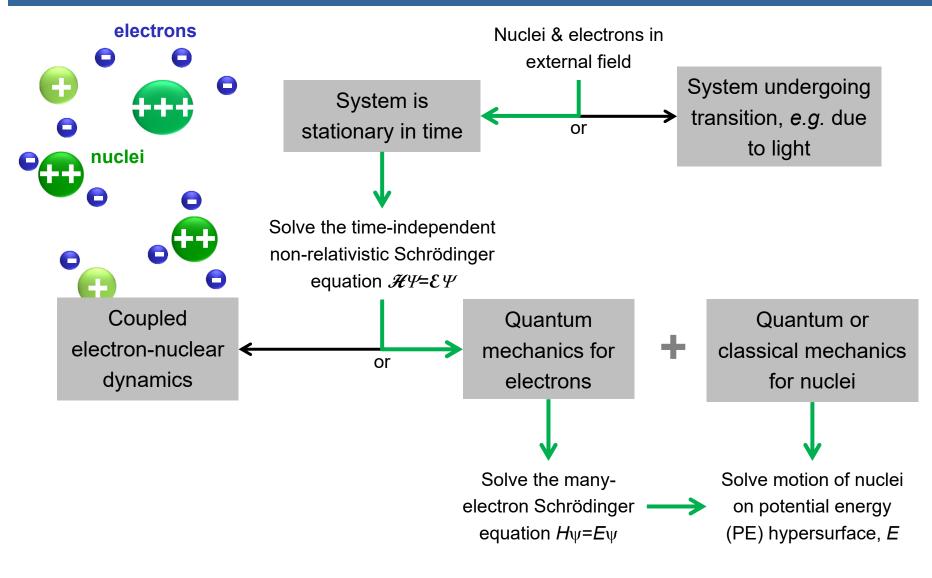




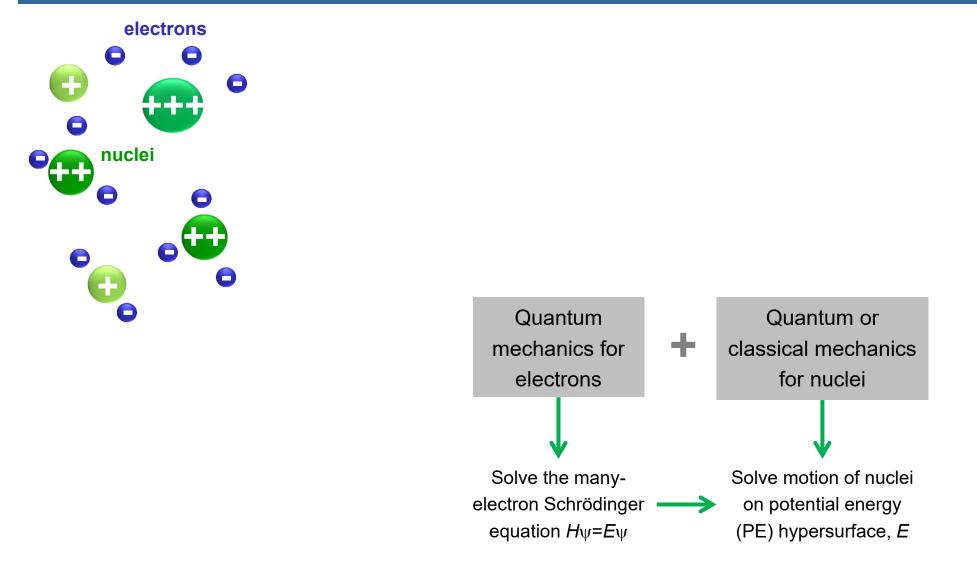




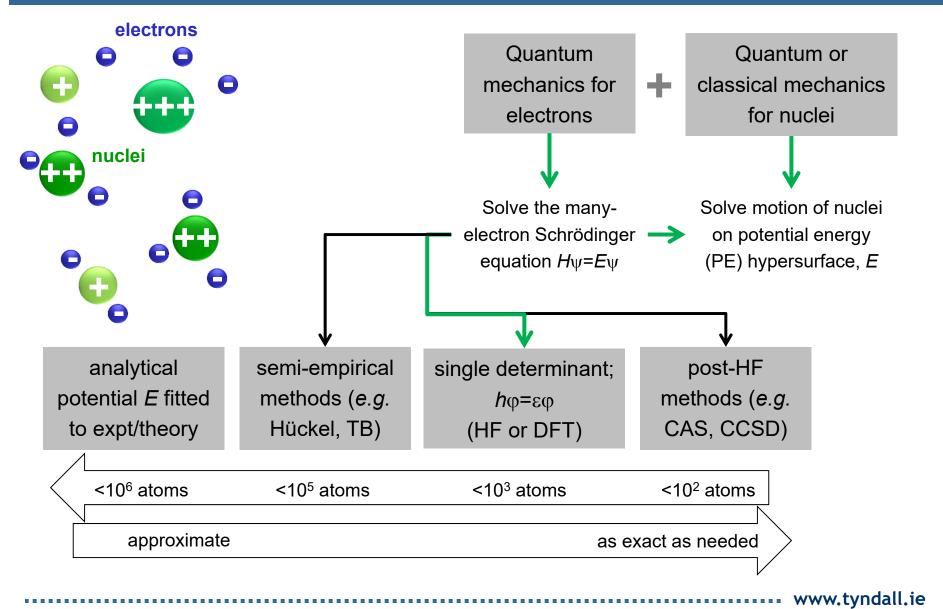














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analytical	semi-empirical	single determinant;	post-HF
potential <i>E</i> fitted	methods (<i>e.g.</i>	<i>h</i> φ=εφ	methods (<i>e.g.</i>
to expt/theory	Hückel, TB)	(HF or DFT)	CAS, CCSD)

Fixed potential energy function, varying only with interatomic geometry.



Analogy: always bring an umbrella, just in case it will rain.

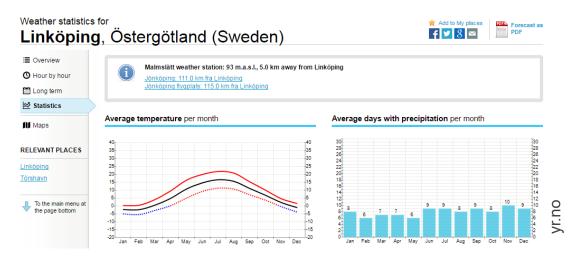


analytical	semi-empirical	mi-empirical single determinant;	
potential <i>E</i> fitted	methods (<i>e.g.</i>	<i>h</i> φ=εφ	methods (<i>e.g.</i>
to expt/theory	Hückel, TB)	(HF or DFT)	CAS, CCSD)

Wavefunction-based description of electrons, but solutions fitted to known data.



Analogy: bring umbrella if weather statistics for this day averaged over many years indicate high likelihood of rain.





analytical	semi-empirical	single determinant;	post-HF
potential <i>E</i> fitted methods (<i>e.g.</i>		μ φ=εφ	methods (<i>e.g.</i>
to expt/theory	Hückel, TB)	(HF or DFT)	CAS, CCSD)

Many-electron wavefunction is anti-symmetric product of many one-electron wavefunctions ("orbitals").

HARTREE-FOCK THEORY:

Solve one-electron problem in mean field due to other electrons

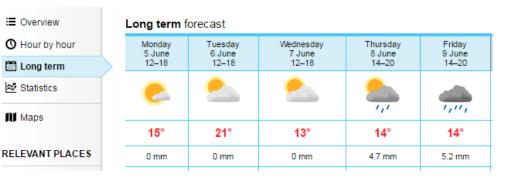
 \rightarrow Missing dynamical correlation

Insist that each orbital is empty or doubly-occupied

 \rightarrow Missing static correlation (e.g. when HOMO=LUMO)

Analogy: bring umbrella if rain is forecast for today.

Long term forecast for Linköping, Östergötland (Sweden)



yr.no



analytical	semi-empirical	single determinant;	post-HF
potential <i>E</i> fitted	methods (<i>e.g.</i>	μ φ=εφ	methods (e.g.
to expt/theory	Hückel, TB)	(HF or DFT)	CAS, CCSD)

Many-electron wavefunction is anti-symmetric product of many one-electron wavefunctions ("orbitals").

DENSITY FUNCTIONAL THEORY:

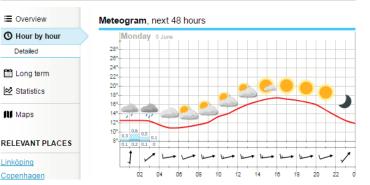
Solve one-particle problem in mean field that mimics electron correlation \rightarrow Some dynamical correlation included

Insist that each orbital is empty or doubly-occupied

 \rightarrow Missing static correlation (e.g. when HOMO=LUMO)

Analogy: bring umbrella if hour-by-hour weather forecast indicates high likelihood of rain now.

Hourly forecast for **Linköping**, Östergötland (Sweden)



yr.no

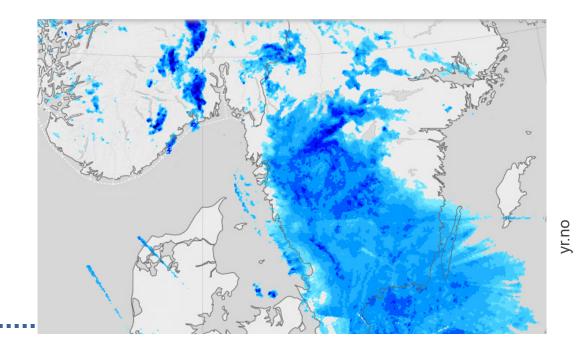


analytical	semi-empirical single determinar		post-HF
potential <i>E</i> fitted	methods (<i>e.g.</i>	<i>h</i> φ=εφ	methods (<i>e.g.</i>
to expt/theory	Hückel, TB)	(HF or DFT)	CAS, CCSD)

Many-electron wavefunction by mixing configurations and/or reference states from single-electron solutions.



Analogy: bring umbrella if radar shows that rain is approaching.



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Reproducibility in density functional theory calculations of solids

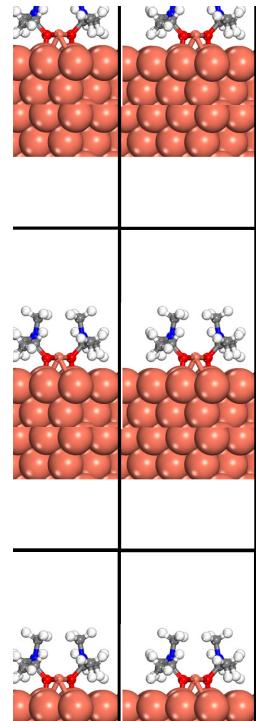
Kurt Lejaeghere^{1,*}, Gustav Bihlmayer², Torbjörn Björkman^{3,4}, Peter Blaha⁵, Stefan Blügel², Volker Blum⁶, Damien Calis...



Science 25 Mar 2016: Vol. 351, Issue 6280, aad3000 DOI: 10.1126/science.aad3000



Lejaeghere *et al.* compared the calculated values for the equation of states for 71 elemental crystals from 15 different widely used DFT codes employing 40 different potentials. Although there were variations in the calculated values, most recent codes and methods converged toward a single value, with errors comparable to those of experiment.

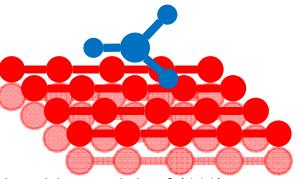


Density functional theory for slabs

10³ atoms per cell

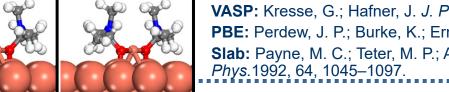
Length scale 10⁻⁹ m

Time scale 10⁻¹² s



Surface represented by infinitely-repeating 4 layer slab of (111)oriented fcc-Cu separated by vacuum;

- VASP program;
- Functional due to Perdew, Burke & Ernzerhof with vdW-optB88 correction;
- Plane waves to 450 eV cutoff;
- PAW treatment of cores;
- k-point at Γ is adequate for large p(6×6) cell with 18 Å vacuum;
- Self consistent steps to 10⁻⁴ eV;
- Geometry optimised by conjugate-gradient;
- Activation energies E_a by nudged elastic band.

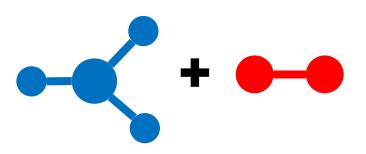


VASP: Kresse, G.; Hafner, J. J. Phys.: Condens. Matter 1994, 6, 8245.
PBE: Perdew, J. P.; Burke, K.; Ernzerhof, M. Phys. Rev. Lett. 1996, 77, 3865–3868.
Slab: Payne, M. C.; Teter, M. P.; Allan, D. C.; Arias, T. A.; Joannopoulos, J. D. Rev. Mod. Phys. 1992, 64, 1045–1097.
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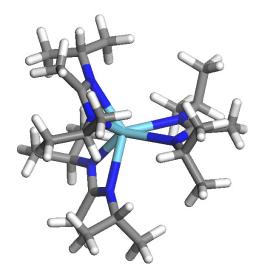


Density functional theory for molecules

10³ atoms in vacuum Length scale 10⁻⁹ m Time scale 10⁻¹² s



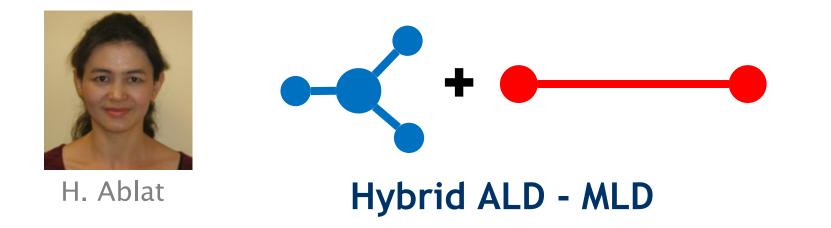
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- Isolated cluster of atoms in gas phase;
- TURBOMOLE program;
- Functional due to Becke & Perdew (1986) or Perdew, Burke & Ernzerhof (1996);
- Basis set of localised atomic orbitals: def2-TZVPP;
- Effective core potentials on heavy atoms;

TURBOMOLE: Ahlrichs, R.; Bär, M.; Häser, M.; Horn, H.; Kölmel, C. *Chem. Phys. Lett.* 1989, 162, 165. Becke, A. D. *Phys. Rev. A* 1988, 38, 3098; Perdew, J. P. *Phys. Rev. B* 1986, 33, 8822. Perdew, J. P.; Burke, K.; Ernzerhof, M. *Phys. Rev. Lett.* 1996, 77, 3865–3868. Eichkorn, K.; Weigend, F.; Treutler, O.; Ahlrichs, R. *Theor. Chem. Acc.* 1997, 97, 119.





TMA + acrylate + ethanolamine

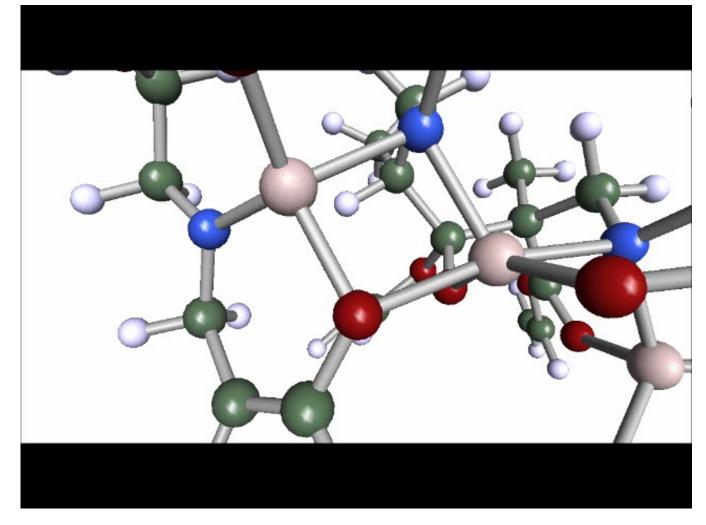




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Bonding in hybrid MLD/ALD films



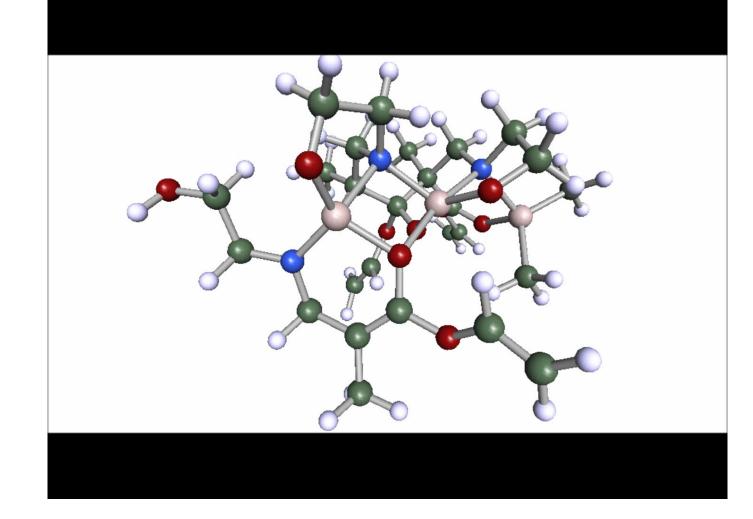
O-Al-N stretch computed at 511 cm⁻¹

...measured with FTIR at 514 cm⁻¹





Bonding in hybrid MLD/ALD films



O-Al-N stretch computed at 610 cm⁻¹

... measured at 610 cm⁻¹ with FTIR



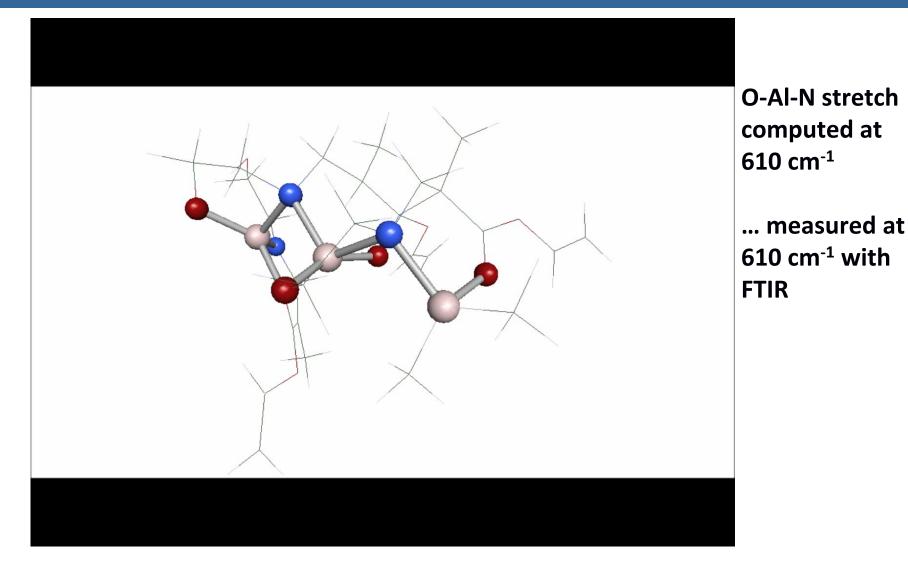


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Bonding in hybrid MLD/ALD films



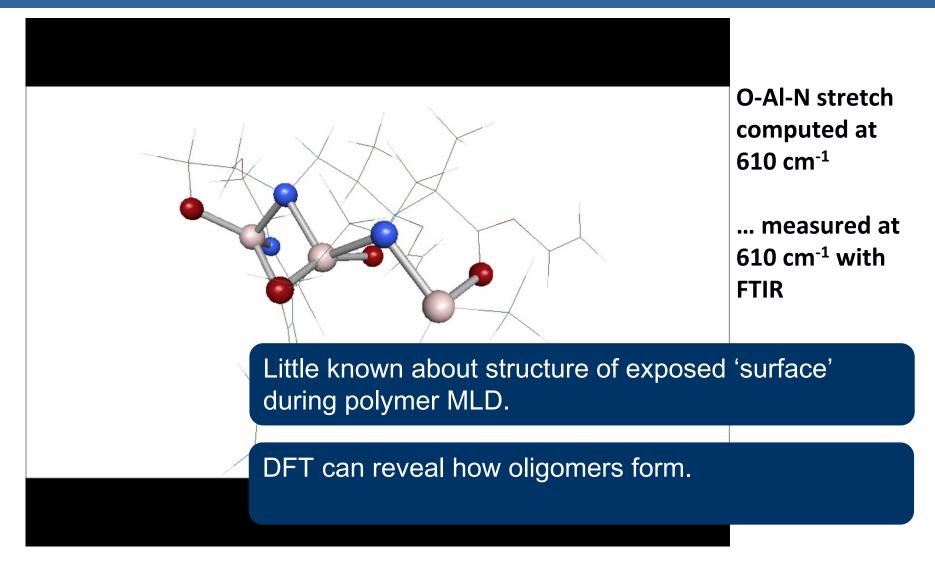
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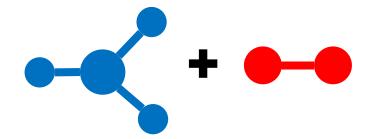
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Bonding in hybrid MLD/ALD films



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Combinatorial approach to precursor design

ALD of Si_3N_4



J. Korean Ceram. Soc. > Volume 53(3); 2016 > Article

Special Issue : Recent Advances in Computational Materials Science Article

Journal of the Korean Ceramic Society 2016; 53(3): 317-324.

Published online: May 31, 2016

DOI: https://doi.org/10.4191/kcers.2016.53.3.317

Quantum Mechanical Simulation for the Analysis, Optimization and Accelerated Development of Precursors and Processes for Atomic Layer Deposition (ALD)

Thomas Jeffrey Lomax Mustard, Hyunwook Shaun Kwak^{*}, Alexander Goldberg, Jacob Gavartin^{**}, Tsuguo Morisato^{***}, Daisuke Yoshidome^{***}, Mathew David Halls[†]

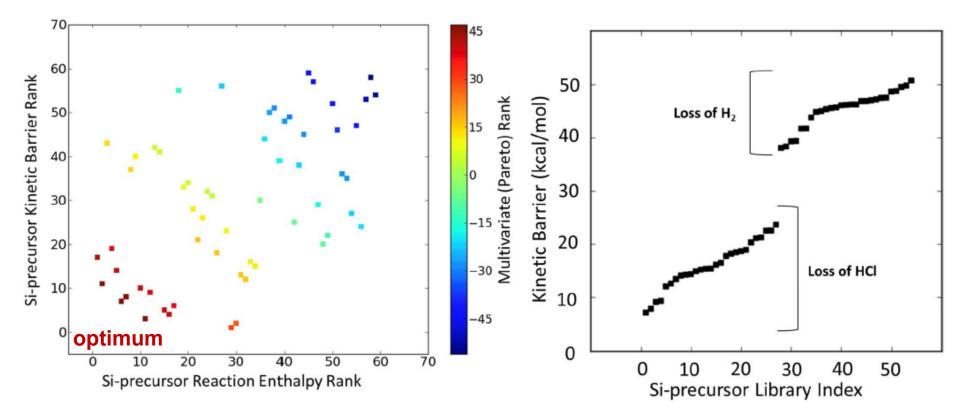
Schrödinger Inc., San Diego, California 92121, United States

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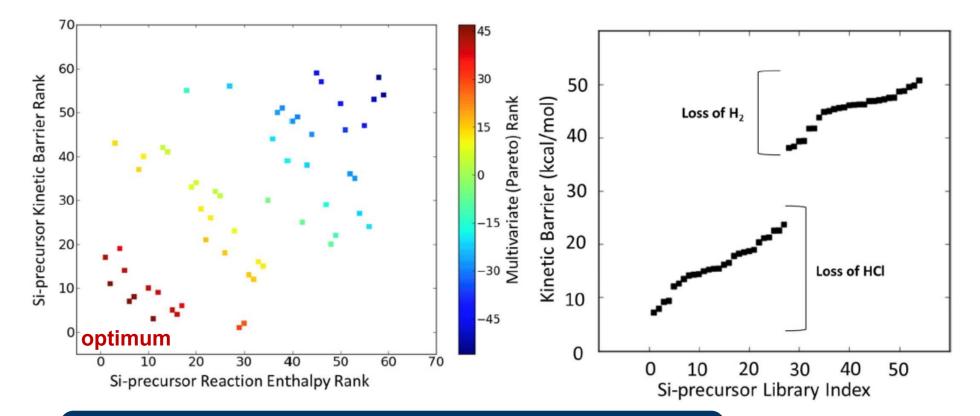
***Schrödinger K.K., Chiyoda-ku, Tokyo 100-0005, Japan

[†]Corresponding author :Mathew David Halls, E-mail : mat.halls@schrodin 299-4532



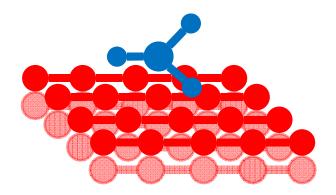
Precursors screened:

Si(Cl)R₂ with R=H, Cl or CH₃ Si₂(Cl)R₅ with R=H or Cl Enthalpy and kinetic barrier evaluated for model reactions: NH_{3 (g)} + Si(Cl)(H)R_{2 (g)} \rightarrow H₂N-Si(H)R_{2 (g)} + HCl (g) NH_{3 (g)} + Si(Cl)(H)R_{2 (g)} \rightarrow H₂N-Si(Cl)R_{2 (g)} + H_{2 (g)}



Knowledge about ALD mechanism allows metrics for precursor design to be defined.

Large numbers of precursors can be automatically generated and screened.



Improved models of substrates and growing surfaces

ALD of Al₂O₃



PCCP



PAPER

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Cite this: Phys. Chem. Chem. Phys., 2015, 17, 17322

First principles study of the atomic layer deposition of alumina by TMA-H₂O-process

Timo Weckman* and Kari Laasonen

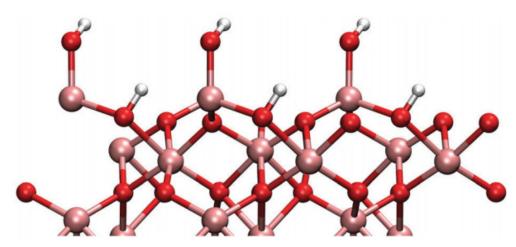
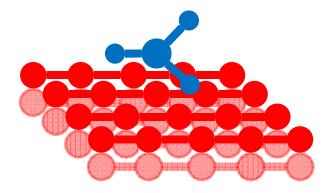


Fig. 1 Side-view of the hydroxylated surfaces formed from dissociatively adsorbed water. Two kinds of hydroxyl groups are present, the higher group formed from the water molecule and the lower one formed with the dissociated hydrogen and surface oxygen. A monolayer coverage is achieved when four water molecules adsorb onto a 2×2 cell which











C. Murray

How adsorption energy affects exposure required for saturation

ALD of Si₃N₄



"Growth rate" in ALD?

Individual reaction steps

- \rightarrow activation energies
- \rightarrow kinetics of individual steps
- \rightarrow kinetics of overall growth process.

Rate at which growth process takes place

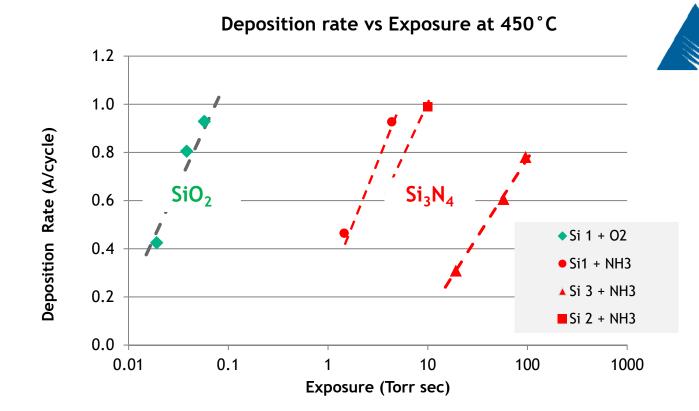
- \rightarrow exposure needed
- \rightarrow dependence of growth on process time
- \rightarrow throughput.

Self-limiting surface chemistry

- \rightarrow saturation
- \rightarrow maximum thickness increment per cycle (GPC).



Reactivity of ALD SiO₂ versus Si₃N₄

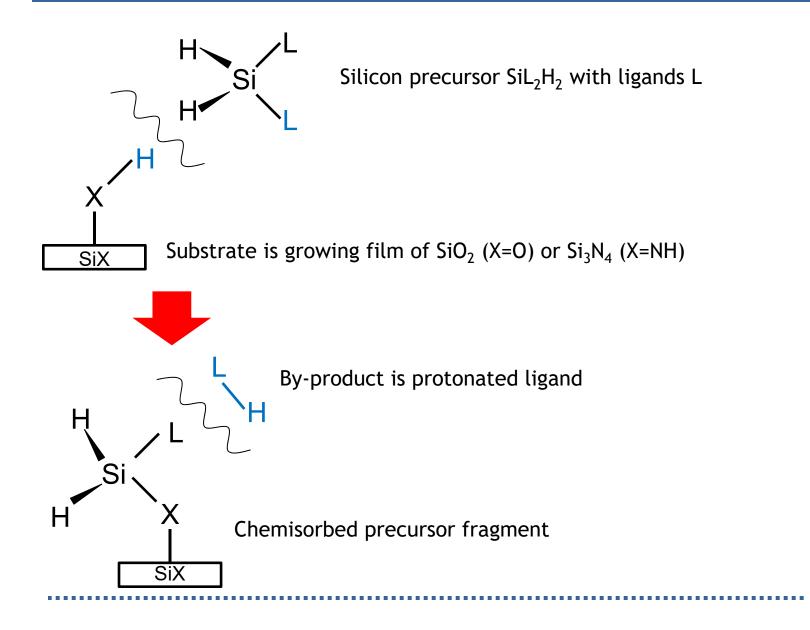


Require 100x greater exposure of Si precursor to achieve saturation for Si_3N_4 relative to SiO_2

What Si precursor can solve this problem?



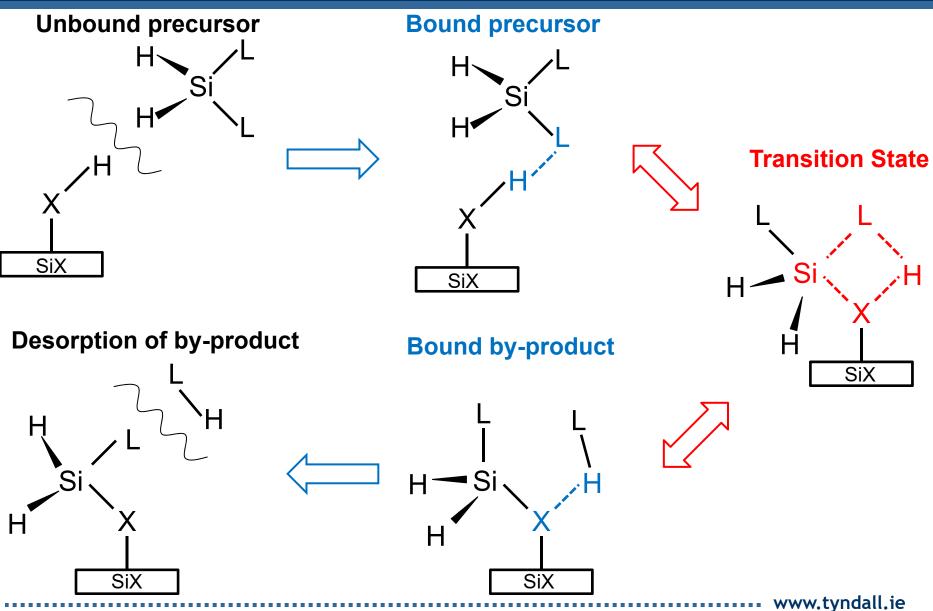
Reactivity of ALD SiO₂ versus Si₃N₄



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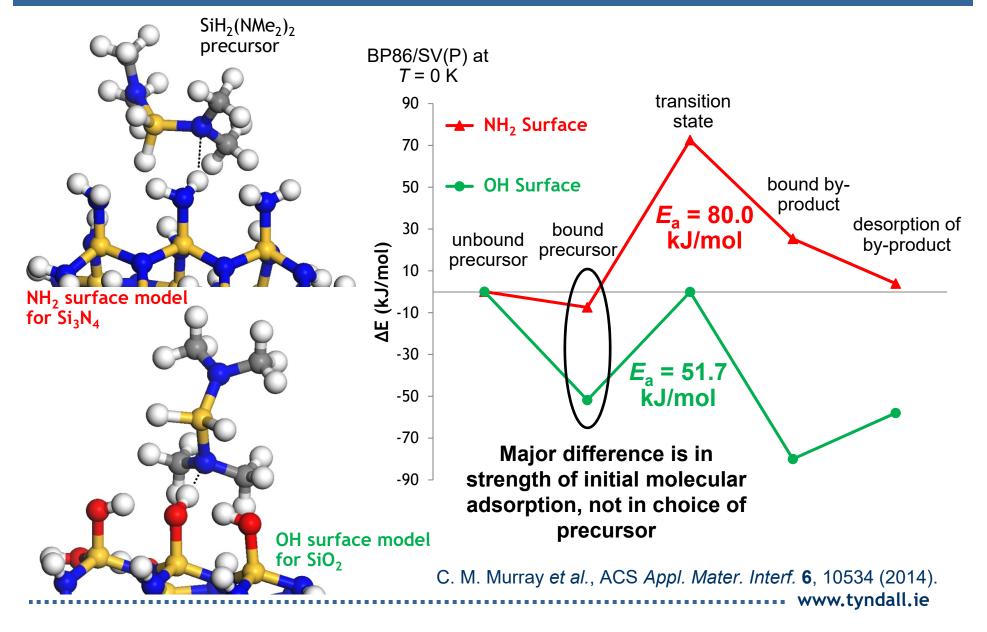


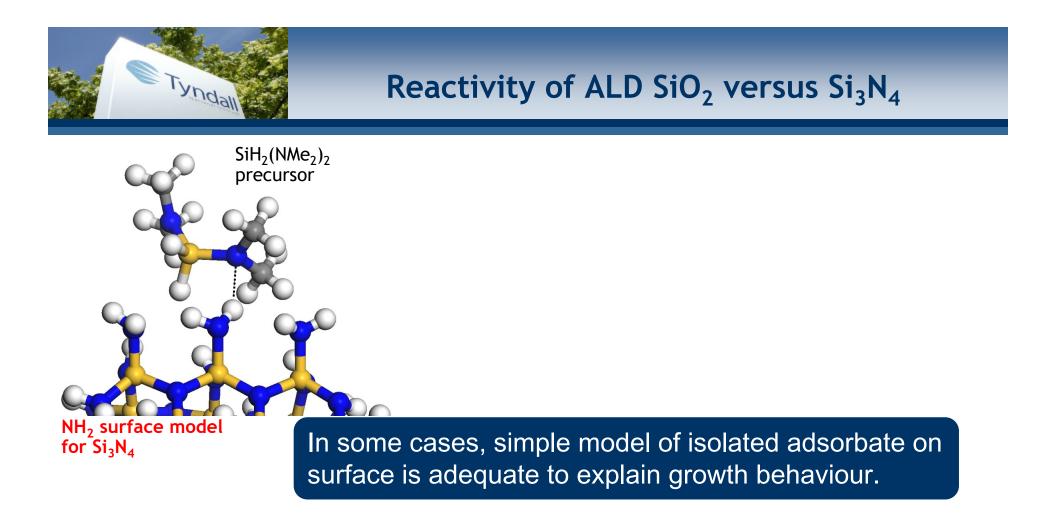
Reactivity of ALD SiO₂ versus Si₃N₄





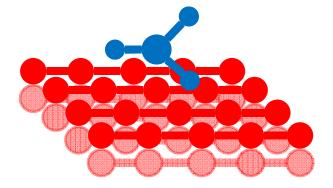
Reactivity of ALD SiO₂ versus Si₃N₄







Accuracy of DFT results







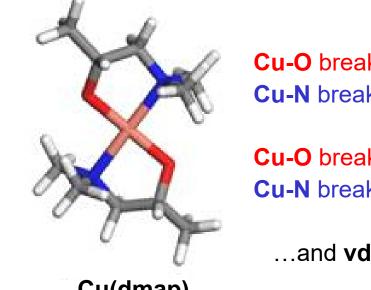
Importance of van der Waals interactions during precursor adsorption

Y. Maimaiti

ALD of Cu



How do Cu precursors adsorb onto the growing Cu surface?



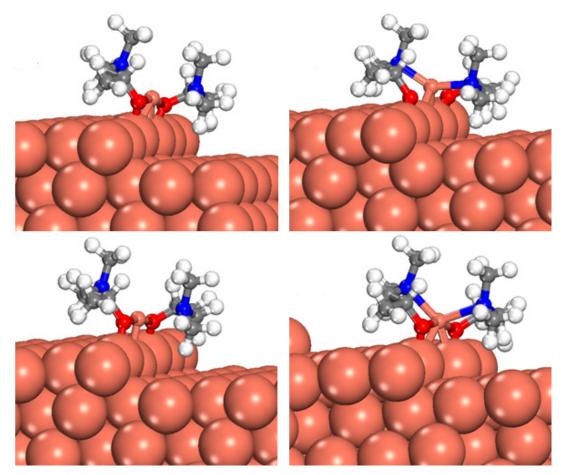
Cu-O break? Cu-N break? → form Cu-Cu Cu-O break? Cu-N break?

...and vdW interactions?

Cu(dmap)₂ dmap=dimethyl-amino-propoxide



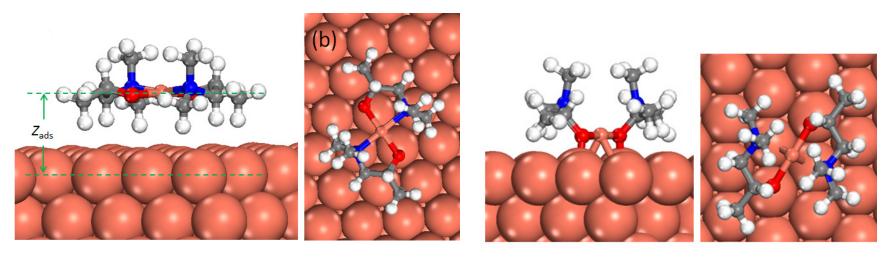
Chemisorption onto edge or kink for all functionals, regardless of vdW treatment:



Y. Maimaiti et al., J. Phys. Chem. C 119, 9375–9385 (2015).



Adsorption onto flat Cu(111) is sensitive to van der Waals forces, alignment of Cu-O and cleavage of Cu-N:



∆*E*(physisorbed)

no sites

- PBE
 -0.4 eV (3 sites)

 vdW-DF2
 -1.0 eV (3 sites)

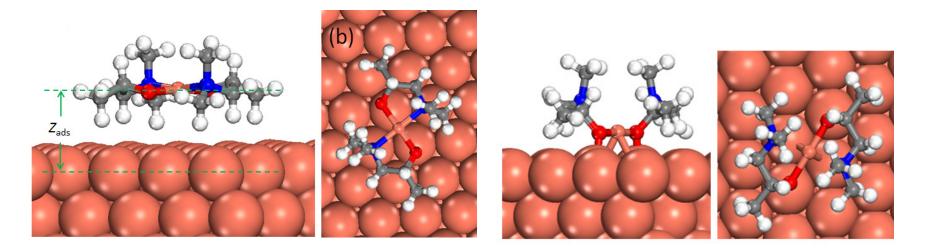
 tB88-vdW
 -1.6 eV (1 site)
- optB88-vdW -1.
 - PBE-D3

- ∆*E*(chemisorbed)
 - -1.5 eV (1 site)
 - -2.0 eV (1 site)
 - -3.2 eV (3 sites)
 - -3.5 eV (4 sites)

Y. Maimaiti et al., J. Phys. Chem. C 119, 9375–9385 (2015).



Adsorption onto flat Cu(111) is sensitive to van der Waals forces, alignment of Cu-O and cleavage of Cu-N:

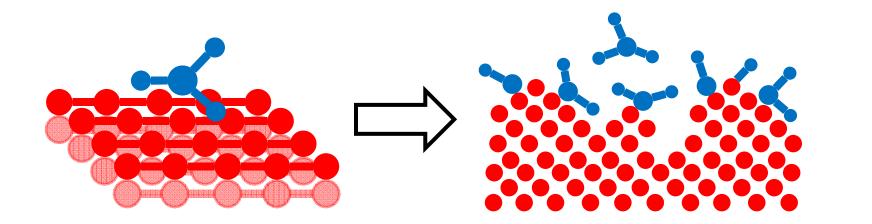


No consensus yet on how best to incorporate vdW contribution to adsorption.

Y. Maimaiti et al., J. Phys. Chem. C 119, 9375–9385 (2015).

Accuracy of DFT results







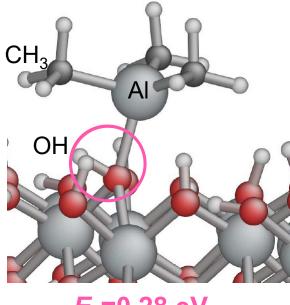
Isolated ligands can persist on surface for entire cycle

ALD of Al_2O_3

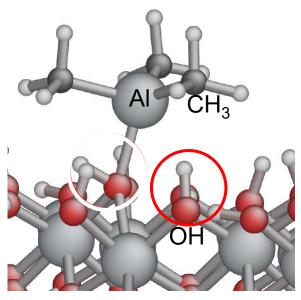




<u>TMA pulse:</u> Computed activation energies for transfer of H⁺ from surface-OH to adsorbate-CH₃, resulting in desorption of CH₄:



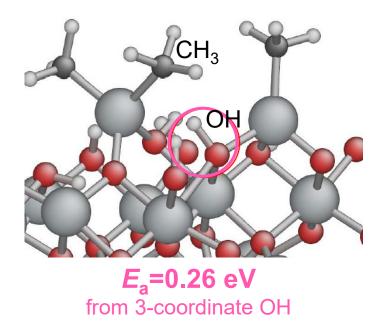
*E*_a=0.28 eV from 3-coordinate OH

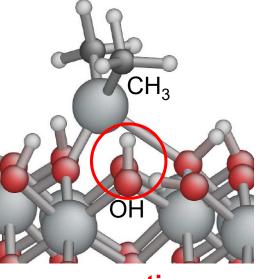


*E*_a=0.74 eV from 2-coordinate OH



TMA pulse: Computed activation energies for transfer of H⁺ from surface-OH to adsorbate-CH₃, resulting in desorption of CH₄:

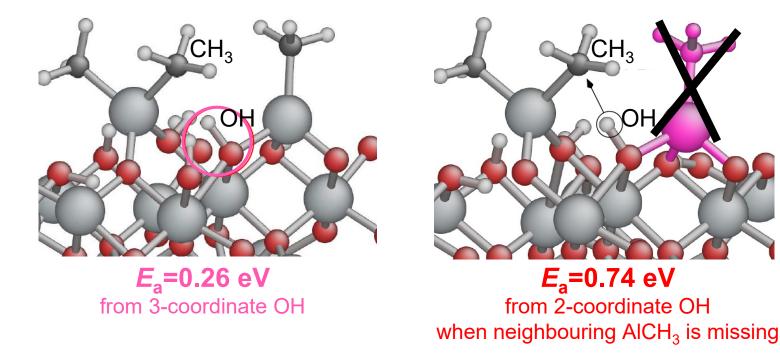




no reaction from 2-coordinate OH

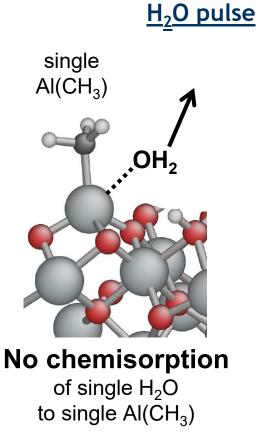


<u>TMA pulse:</u> Computed activation energies for transfer of H⁺ from surface-OH to adsorbate-CH₃, resulting in desorption of CH₄:

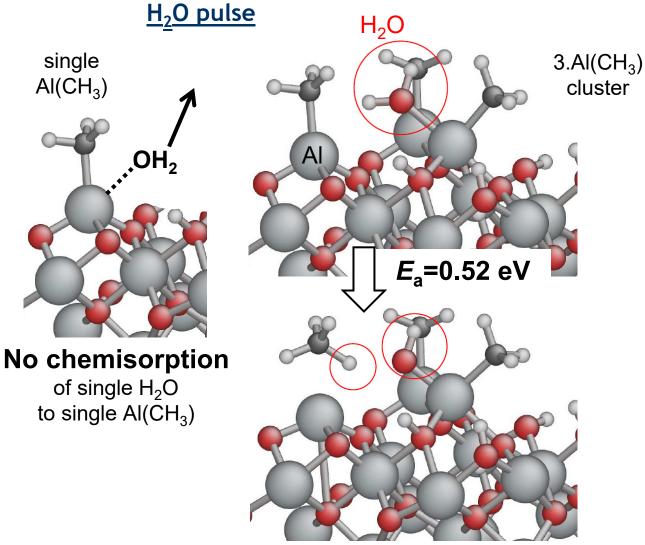


<u>Cooperative effect:</u> neighbouring adsorbate increases coordination number of O and thus increases Brønsted acidity of OH.





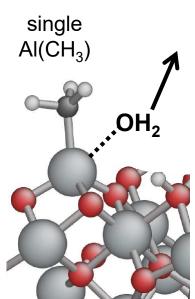




large grey=Al, red=O, white=H, small grey=C



<u>H₂O pulse</u>



No chemisorption of single H_2O

to single $AI(CH_3)$

 $3.AI(CH_3)$ cluster A *E*_a=0.52 eV

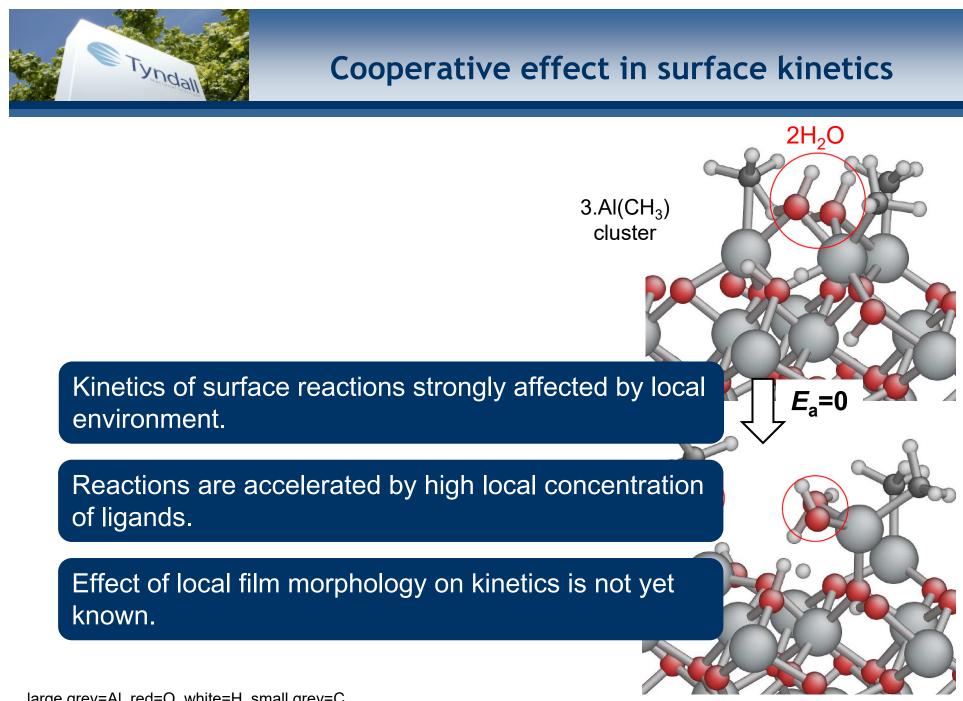
 H_2O

large grey=Al, red=O, white=H, small grey=C

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 $2H_2O$

*E*_a=0



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large grey=Al, red=O, white=H, small grey=C



Published Online: January 2016 Accepted: December 2015

What is limiting low-temperature atomic layer deposition of Al₂O₃? A vibrational sum-frequency generation study

D V. Vandalon^{a)} and W. M. M. Kessels^{a)}

Appl. Phys. Lett. 108, 011607 (2016); doi: http://dx.doi.org/10.1063/1.4939654

PDF	ABSTRACT	FULL TEXT	FIGURES	SUPPLEI
Atomic layer deposition Che	mical reaction cro	ss sections	Hydrogen	reactions

ABSTRACT

The surface reactions during atomic lay $Al(CH_3)_3$ and H_2O have been studied wit to reveal what is limiting the growth at

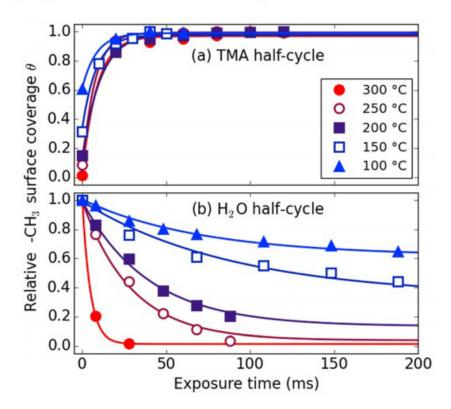
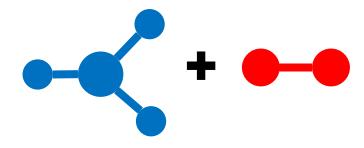




FIG. 3. Relative –CH₃ surface coverage θ , extracted from the BB-SFG spectra as a function of TMA and H₂O exposure for various temperatures. The solid lines represent fits to the data in order to extract information about the reaction kinetics.



What theory can tell us about ALD mechanism



SUCCESSES: Screening based on intrinsic chemistry; Oligomer formation during MLD

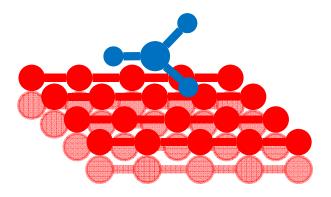
CHALLENGES: Volatility? Thermal stability?



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What theory can tell us about ALD mechanism



SUCCESSES:

Sketch out reaction mechanism;

Account for many experimental anomalies

CHALLENGES:

Accuracy of weak interactions;

Need more realistic surface geometries for kinetics

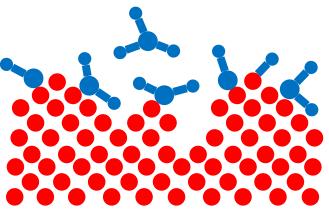


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What theory can tell us about ALD mechanism



SUCCESSES:

More accurate activation energies; Indications of how morphology evolves

CHALLENGES: **Automatic search?**



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